	L#	Hits	Search Text	DBs
1	L1	1351	430/321.ccls.	US- PGPUB; USPAT
2	L2	17914	waveguide.ti,ab.	US- PGPUB; USPAT
3	L3	124	1 and 2	US- PGPUB; USPAT
4	L4	289214	(polymer or organic or polymeric or photosensitiv\$6 or photopolymeri\$6 or photoresist or polymeriz\$6 or polymeris\$6 or resist).ti,ab.	US- PGPUB; USPAT
5	L5	1050	2 and 4	US- PGPUB; USPAT
6	L6	157	"o.sub.2") same (vacuum or pressure or	US- PGPUB; USPAT
7	L7	60354	(polymeriz\$6 or polymeris\$6 or cure\$1	US- PGPUB; USPAT
8	L8	127	5 and 7	US- PGPUB; USPAT
9	L9	555	385/143,145.ccls.	US- PGPUB; USPAT
10	L10	2151	385/129,130.ccls.	US- PGPUB; USPAT
11	L11	249072	photoresist or resist or expos\$4 or	US- PGPUB; USPAT
12	L12	299	10 and 4	US- PGPUB; USPAT
13	L13	221	12 not (3 or 8 or 6)	US- PGPUB; USPAT
14	L14	228341	liquid.ti,ab.	US- PGPUB; USPAT

	L#	Hits	Search Text	DBs
15	L15	57	2 and 4 and 14	US- PGPUB; USPAT
16	L16	101	9 and 11	US- PGPUB; USPAT
17	L17	318327	proximity	US- PGPUB; USPAT
18	L18	2114	2 and 17	US- PGPUB; USPAT
19	L19	29666	17 with (imag\$4 or expos\$4 or mask\$4 or photomask\$4 or reticle or pattern\$4 or photolith\$10 or lithograph\$6 or radiat\$4 or irradiat\$4)	US- PGPUB; USPAT
20	L20	310	2 and 19	US- PGPUB; USPAT
21	L21	21161	17 near8 (imag\$4 or expos\$4 or mask\$4 or photomask\$4 or reticle or pattern\$4 or photolith\$10 or lithograph\$6 or radiat\$4 or irradiat\$4)	US- PGPUB; USPAT
22	L22	47	5 and 21	US- PGPUB; USPAT
23	L23	362010	mask\$4 or photomask\$4 or reticle	US- PGPUB; USPAT
24	L24	556895	oxygen\$6 or deoxygen\$6 or o2 or "o.sub.2"	US- PGPUB; USPAT
25	L25	10393	23 with 24	US- PGPUB; USPAT
26	L26	29	5 and 25	US- PGPUB; USPAT
27	L27	14	ferm-paul\$4	US- PGPUB; USPAT
28	L28	3	battell-kevin\$.in.	US- PGPUB; USPAT

	L#	Hits	Search Text	DBs
29	L29	45	beeson-karl\$.in.	US- PGPUB; USPAT
30	L31	22	maxfield-macrae\$.in.	US- PGPUB; USPAT
31	L32	55	shacklette-lawrence\$.in.	US- PGPUB; USPAT
32	L35	7	pant-deepti\$.in.	US- PGPUB; USPAT
33	L36	46	(27 or 28 or 29 or 31 or 32 or 35) and 2	US- PGPUB; USPAT

	L#	Hits	Search Text	DBs
1	L1	7416	Mavediline cim	US- PGPUB
2	L2	114126	(polymer or organic or polymeric or photosensitiv\$6 or photopolymer\$8 or photoresist or polymeriz\$8 or polymeris\$8 or resist).clm.	US- PGPUB
3	L3	34714	K 30	US- PGPUB
4	L4	111	TI and Jand 3	US- PGPUB
5	L5	1988	"I DOWNERS AN OF DOWNERS NO OF CUITANT	US- PGPUB
6	L6	3	4 and 5	US- PGPUB